

WAFER HANDLER METHOD AND SYSTEM

BACKGROUND

(1) Field

[0001] The disclosed methods and systems relate generally to semiconductor processing, and more particularly to wafer handling methods and systems.

(2) Description of Relevant Art

[0002] Some challenges of semiconductor manufacturing include providing a manufacturing process that produces reduced process defects with increased process throughput. These manufacturing concerns can also be balanced with other requirements that include a need for reduced contamination.

[0003] Figure 18 provides one semiconductor wafer processing system **10** where, for example, a cassette of semiconductor wafers (“wafers”) can be presented to left and right load locks **12, 14** to allow wafer transfers to a processing chamber **16** such as, for example, an ion implantation chamber. The load locks **12, 14** can be understood to be an interface between a loading station and the processing chamber **16**. Because the wafers can be loaded from a loading station that may often be at atmospheric pressure, once the wafers are presented to the load locks **12, 14**, the lock loads **12, 14** can be isolated from the loading station and the processing chamber **16**. A load lock vacuum pump, for example, can thus reduce the load lock pressure, or “evacuate” a respective load lock **12, 14**, in accordance with, or to be consistent with the processing chamber pressure.

[0004] Wafers from the cassettes in the left and right load locks **12, 14** can be processed in turn, alternating between left and right load locks **12, 14**. Accordingly, in a system according to Figure 18, the left and right load locks **12, 14** can be substantially simultaneously evacuated and thereafter opened or otherwise interfaced to the processing chamber **16**. For exemplary purposes, a left arm **18** can retrieve a wafer from the left load lock cassette, and present the retrieved wafer

1 to a left orienter 20 that can locate a wafer notch to align the wafer center with the orienter axis
2 of centricity. The left arm 18 can thereafter deliver the wafer to a platen 22 in the process
3 chamber 16, and thereafter, the left arm 18 can be displaced to allow wafer processing. Once the
4 wafer is processed, the left arm 18 can deliver the wafer from the platen 22 to the left orienter 20
5 and hence to the left load lock cassette. As Figure 18 indicates, a wafer from the right load lock
6 cassette can be retrieved by a right robot 24 and placed on a right orienter 26 before being
7 delivered to the platen 22 for processing. Such wafer can also be returned to the right load lock
8 14 after processing is complete. As provided previously herein, throughput for a system
9 according to Figure 18 can be improved by coordinating the alternating delivery of wafers from
10 the left and right load lock cassettes to reduce delay between deliveries to the platen 22.

11 [0005] For a system according to Figure 18, once the wafers from the left and right load lock
12 cassettes are processed and returned to the load lock cassettes, the load locks 12, 14 can be
13 isolated from the processing chamber 16 to allow a substantially simultaneous venting of the load
14 locks 12, 14 and a return to a pressure according to, or otherwise consistent with the loading
15 station pressure. The interfaces between the respective load locks 12, 14 and the loading
16 station(s) can then be opened to allow transfer of the left and right cassettes in accordance with a
17 processing methodology.

18 [0006] Batch vacuum load locks such as those according to Figure 18 can experience poor
19 cycle time because the larger volume of a batch load lock can present a longer evacuation time,
20 during which wafers are being processed from neither the left nor right load locks 12, 14.

21 22 SUMMARY

23 [0007] The systems and methods disclosed herein can include wafer handling methods and
24 systems for retrieving wafers from a storage position, delivering the wafers to a process chamber
25 and returning the processed wafers to the storage position a method for handling wafers can
26 include retrieving a first wafer from a wafer cassette using a first arm, transferring the first wafer
27 from the first arm to a second arm, delivering the first wafer for processing using the second arm

1 so as to generate a processed wafer, removing the processed wafer from processing using the first
2 arm and returning the processed wafer to the storage position using the first arm.

3 **[0008]** The method can include delivering the first wafer using the second arm while
4 retrieving a next wafer from the storage position using the first arm. The first wafer can be
5 oriented prior to being transferred. The method can further include processing the first wafer in
6 the process chamber, wherein processing can include performing photoresist, dry etch, ion
7 implantation, chemical deposition, and/or diffusion. Processing can also include orienting the
8 next wafer and/or transferring the next wafer from the first arm to the second arm.

9 **[0009]** The storage position can be a wafer cassette and retrieving the first wafer or returning
10 the processed wafer can include indexing the cassette.

11 **[0010]** Returning the processed wafer using the first arm can include delivering the next
12 wafer for processing using the second arm or placing the second arm in a standby position.
13 Transferring the wafers between arms can include aligning the first arm and the second arm to
14 facilitate the transfer. Transferring can include controlling an orienter to transfer the first wafer
15 from the first arm to the second arm.

16 **[0011]** In another embodiment a method for handling wafers can include retrieving a first
17 wafer from a wafer cassette using a first arm, transferring the first wafer from the first arm to a
18 second arm, delivering the first wafer for processing using the second arm while retrieving a
19 distinct next wafer from the wafer cassette using the first arm, processing the first wafer to
20 generate a processed wafer, while transferring the next wafer from the first arm to the second
21 arm, removing the processed wafer from processing using the first arm and delivering the next
22 wafer for processing using the second arm while returning the processed wafer to the cassette
23 using the first arm.

24 **[0012]** The method can include retrieving a distinct next wafer from the cassette using the
25 first arm while processing the next wafer, and iteratively performing the processing, removing,
26 and delivering. Processing can include performing photoresist, dry etch, ion implantation,
27 chemical deposition, and/or diffusion. Transferring can include controlling an orienter to transfer

1 the first wafer between the first arm and the second arm. Retrieving can include indexing the
2 cartridge.

3 **[0013]** In a further embodiment, a method for processing wafers from two or more load locks
4 can include processing wafers from a first wafer cassette in a first load lock, where the wafers are
5 delivered for processing from the first wafer cassette using two arms, performing load lock
6 processing for at least a second load lock to obtain a processed load lock while processing the
7 wafers of the first wafer cassette, completing the processing of the first wafer cassette and
8 processing wafers from a second wafer cassette in the processed load lock, where the wafers are
9 delivered for processing from the second wafer cassette using two arms. The method can include
10 performing load lock processing of the first load lock upon completion of processing of the first
11 wafer cassette. Additionally, the method can include performing load lock processing of the first
12 load lock upon completion of processing of the first wafer cassette, completing the processing of
13 the second wafer cassette and processing wafers from a replacement wafer cassette in the first
14 load lock, where the wafers are delivered for processing from the replacement wafer cassette
15 using two arms. Performing load lock processing can include evacuating, venting, isolation,
16 cassette removal, cassette replacement, cassette installation, and/or lock valve control.

17 **[0014]** In one embodiment a system for handling wafers can include a first arm for handling
18 wafers, a distinct second arm for handling wafers, a first cassette of wafers and a wafer
19 processing system.

20 **[0015]** The wafers can be delivered to the processing system from the first cassette using the
21 first arm and the second arm, and the delivery can include individually retrieving a first wafer
22 from the cassette using the first arm, transferring the first wafer from the first arm to the second
23 arm, delivering the first wafer for processing by the wafer processing system using the second
24 arm, processing the first wafer to generate a processed wafer, while retrieving a next wafer from
25 the cassette using the first arm, transferring the next wafer to the second arm, removing the
26 processed wafer using the first arm and delivering the next wafer for processing using the second
27 arm, processing the next wafer to generate a processed wafer while returning the processed wafer

1 to the cassette and iteratively performing the processing, transferring, removing, and processing
2 to process the wafers in the cassette.

3 **[0016]** The system can include a first load lock for the first cassette, an orienter for orienting
4 the wafers before processing and transferring the wafers between the first arm and the second
5 arm and a platen for retrieving wafers from the second arm for delivering the wafers, and
6 transferring processed wafers to the first arm for removing the processed wafers.

7 **[0017]** In a further embodiment a method for handling wafers can include retrieving a next
8 wafer from a selected cassette using a first arm, transferring the next wafer to a second arm,
9 removing a processed wafer from a process system using the first arm, delivering the next wafer
10 to the process system using the second arm and returning the processed wafer to the selected
11 cassette using the first arm.

12 **[0018]** In one aspect, the method can iteratively return to retrieving. Transferring can include
13 using an orienter to transfer the next wafer. The processed wafer can be oriented before returning
14 the processed wafer and a cassette can be selected prior to retrieving. The method can determine
15 whether unprocessed wafers remain in the selected cassette, and, based on the determination, can
16 select a new cassette and iteratively return to retrieving, and/or perform load lock processing
17 associated with the processed cassette.

18 **[0019]** In one embodiment, a method for handling wafers can include retrieving a next wafer
19 from a storage position using a first arm, removing a processed wafer from processing using a
20 second arm, delivering the next wafer for processing, returning the processed wafer to the storage
21 position, and iteratively performing the retrieving, delivering and returning while alternating
22 using the first arm and the second arm between iterations. Returning can include returning while
23 processing the next wafer in a process chamber. Processing can include performing at least one
24 of photoresist, dry etch, ion implantation, chemical deposition, and diffusion. The method can
25 include orienting the next wafer prior to delivering the next wafer. The storage position can be a
26 wafer cassette, and retrieving and returning the processed wafer to the cassette can include
27 indexing the cassette. Returning the processed wafer to the storage position using the second
28 arm can include placing the first arm in a standby position.

1 **[0020]** In one embodiment, a method for handling wafers can include retrieving a first wafer
2 from a wafer cassette using a first arm while removing a processed wafer from processing using a
3 second arm, delivering the first wafer for processing, returning the processed wafer to the wafer
4 cassette while processing the first wafer to generate a processed wafer, retrieving a next wafer
5 from the wafer cassette using the second arm while removing the processed wafer from
6 processing using the first arm, delivering the next wafer for processing, returning the processed
7 wafer to the wafer cassette while processing the next wafer to generate a next processed wafer,
8 and iteratively performing the retrieving, delivering and returning while alternating using the first
9 arm and the second arm between iterations. The method can include orienting the first wafer
10 prior to delivering the first wafer, and orienting the next wafer prior to delivering the next wafer.
11 Retrieving can include indexing the cassette. Delivering the first and next wafers can include
12 processing the first and next wafers in a process chamber and processing can include performing
13 at least one of photoresist, dry etch, ion implantation, chemical deposition, and diffusion.

14 **[0021]** In one embodiment, a system for handling wafers can include a first arm for handling
15 wafers, a distinct second arm for handling wafers, a first cassette of wafers, and a wafer
16 processing system, where wafers are delivered to the processing system from the first cassette
17 using the first arm and the second arm, and where the delivery includes, individually retrieving a
18 first wafer from the cassette using the first arm, delivering the first wafer for processing by the
19 wafer processing system using the first arm, returning a processed wafer to the cassette using a
20 second arm while processing the first wafer to generate a processed wafer, retrieving a next wafer
21 from the cassette using the second arm, removing the processed wafer using the first arm and
22 delivering the next wafer for processing using the second arm, processing the next wafer to
23 generate a processed wafer while returning the processed wafer to the cassette, and iteratively
24 performing the retrieving, delivering, returning, retrieving, removing, and processing to process
25 the wafers in the cassette.

26 **[0022]** The system can include a first load lock for the first cassette and an orienter for
27 orienting the wafers before processing. The system can include a platen for retrieving wafers
28 from the first and second arms for processing the wafers, and transferring processed wafers to the

1 first and second arms for removing the processed wafers. The system can include at least one
2 carriage for moving the first and second arms relative to the cassette for returning and retrieving
3 wafers from the cassette.

4 **[0023]** Other objects and advantages will become apparent hereinafter in view of the
5 specification and drawings.

6 7 BRIEF DESCRIPTION OF THE DRAWINGS

8 **[0024]** FIG. 1 illustrates a system that includes a first and second arm for handling wafers;
9 FIG. 2 illustrates a first arm in a load lock retrieval position, with a second arm in a
10 standby position;
11 FIG. 3 illustrates the first arm in an orienter position, with the second arm in a
12 standby position;
13 FIG. 4 illustrates the first and second arms in the orienter positions for a delivery of
14 an initial wafer for processing;
15 FIG. 5 illustrates the first arm in a load lock retrieval position, with the second arm in
16 a process position;
17 FIG. 6 illustrates the first arm in the orienter position, with the second arm in a
18 standby position;
19 FIG. 7 illustrates the first and second arms in the orienter positions for a delivery of a
20 non-initial wafer for processing;
21 FIG. 8 illustrates the first arm in a platen retrieval position, with the second arm in a
22 process position;
23 FIG. 9 illustrates the first arm in an orienter position, with the second arm in a process
24 position;
25 FIG. 10 illustrates the first arm in a load lock delivery position, with the second arm
26 in a standby position;
27 FIG. 11 illustrates the first arm in an orienter position, with the second arm in a
28 standby position;

FIG. 12 illustrates the first arm in a load lock retrieval position, with the second arm in a standby position;

FIG. 13 illustrates the first arm in an orienter position, with the second arm in a standby position;

FIG. 14 illustrates the first and second arms in the orienter positions for a delivery of a non-initial wafer for processing;

FIG. 15 illustrates a block diagram for one disclosed system and method;

FIGS. 16A-16C illustrate an embodiment of a system that includes a first and second arm for handling wafers;

FIG. 17 illustrates a block diagram for another disclosed system and method; and,

FIG. 18 illustrates a prior art system.

DESCRIPTION

[0025] To provide an overall understanding, certain illustrative embodiments will now be described; however, it will be understood by one of ordinary skill in the art that the systems and methods described herein can be adapted and modified to provide systems and methods for other suitable applications and that other additions and modifications can be made without departing from the scope of the systems and methods described herein.

[0026] Unless otherwise specified, the illustrated embodiments can be understood as providing exemplary features of varying detail of certain embodiments, and therefore, unless otherwise specified, features, components, modules, and/or aspects of the illustrations can be otherwise combined, separated, interchanged, and/or rearranged without departing from the disclosed systems or methods. Additionally, the shapes and sizes of components are also exemplary and unless otherwise specified, can be altered without affecting the disclosed systems or methods.

[0027] The disclosure includes wafer handling methods and systems for retrieving wafers from a wafer cassette in a load lock, delivering the wafers to a process chamber, and returning the processed wafers to the cassette. The methods and systems include a first arm and a second arm that can be coordinated to perform the retrieval, delivery, and return of wafers to allow wafers from the same cassette and/or load lock to be sequentially processed. As provided herein, sequential processing is not to be understood as implying an order of retrieval from the cassette.

[0028] Accordingly, for the disclosed methods and systems, a first arm for handling wafers can be understood to be a robotic or other mechanical, electrical, and/or electro-mechanical arm that may be capable of handling wafers as provided herein. The first arm can be of varying shape such as c-shaped, u-shaped, or another shape, and the methods and systems herein are not limited by a type and/or shape of arm, or a method or system by which the arm may be controlled. The methods and systems also include a second arm. Although the illustrated embodiments indicate that the second arm can be the same as the first arm, one of ordinary skill will recognize that the first arm and the second arm can have a different shape, structure, components, and methods, and may have a different controller from the first arm, although in an embodiment where different

1 controllers may be used, such first arm and second arm controllers can be coordinated to provide
2 a method and system as provided herein.

3 **[0029]** Although the figures presented herein illustrate two load locks referred to as left and
4 right load locks **12, 14**, the disclosed methods and systems are not so limited, and include
5 methods and systems with one or more load locks. Further, it can be understood that for the
6 illustrated embodiments that indicate two load locks and where the methods and systems are
7 described relative to the left load lock **12**, such methods and systems can also be applied to the
8 right load lock **14**.

9 **[0030]** Figure 1 shows one embodiment according to the disclosed methods and systems for
10 handling wafers that includes left and right load locks **12, 14**. As provided herein, the methods
11 and systems will be described relative to the left load lock **12** with the understanding that the
12 methods and systems can be applied to the right load lock **14**. The Figures illustrate positions
13 that may be engaged by a first arm **18** and a second arm **30** that can access the left load lock **12**.
14 As will be provided herein, the first arm **18** can be positioned in positions that include at least a
15 load lock position to allow the first arm **18** to retrieve and/or return a wafer from/to the cassette
16 **32** in the left load lock **12**, an orienter position to allow the first arm **18** to interface with at least
17 an orienter **20**, and a process position to allow the first arm **18** to retrieve a wafer from a process
18 chamber **16**. Those of ordinary skill will recognize that the methods and systems can be applied
19 to various process systems for delivering wafers to process chambers that perform, for example,
20 at least one of photoresist, dry etch, ion implantation, chemical deposition, and diffusion,
21 although such examples are provided for illustration and not limitation, and other processing can
22 be performed in the process chamber **16**. Although the illustrated embodiments indicate the use
23 of wafer cassette **32**, one of ordinary skill will recognize that other wafer storages means that that
24 can present wafers for retrieval from a storage position such as a load lock can be employed and
25 that the systems and methods described herein can be adapted for use therewith.

26 **[0031]** The second arm **30** can be positioned in positions that include at least a standby
27 position to allow the second arm **30** to not interfere with processing of a wafer or with the first
28 arm's interaction with the orienter **20**, an orienter position to allow the second arm **30** to interface

1 with at least the orienter **20**, and a process position to allow the second arm **30** to deliver a wafer
2 to the process chamber **16**. Accordingly, based on an embodiment, a standby position and an
3 orienter position may be the same position for the second arm **30**. One of ordinary skill thus
4 recognizes that unlike the other arm positions described herein that can be based on, for example,
5 the orienter, the load lock, and a platen, the standby position is not so defined and may include a
6 number of positions, including other defined positions.

7 **[0032]** It can thus be recognized that the first arm **18** and the second arm **30** include orienter
8 positions and process chamber positions, and as provided herein, vertical transfers of wafers
9 between the first arm **18** and the second arm **30** can be performed while such arms **18, 30** may be
10 maintained in such positions. Accordingly, the first arm **18** and the second arm **30** can be
11 arranged to allow a distance that facilitates independent operation when vertically aligned, while
12 recognizing that a reduced vertical distance between the first and second arms **18, 30** may reduce
13 processing time to transfer wafers between the same. Although such vertical distance between
14 such arms **18, 30** can thus vary based on system characteristics, in one embodiment, when
15 vertically aligned, the first and second arms **18, 30** can be separated by less than approximately
16 five-eighths to one-half of one inch.

17 **[0033]** Returning again to Figure 1, one of ordinary skill may recognize that the chamber **16**
18 is shown to be enlarged to accommodate the second arm **30** which may be understood to be
19 illustrated in one of the aforementioned standby positions. It can be understood that such
20 enlargement of the process chamber **16** is optional, and in some embodiments, such enlargement
21 may not be necessary to accommodate one or more standby positions for the second arm **30**.

22 **[0034]** As one of ordinary skill in the art also recognizes, the cassette **32** can be introduced to
23 the load lock **12** via a loading station, where the load lock can be isolated from the loading
24 station and the process chamber **16** to allow the load lock pressure to be altered according to
25 (e.g., to be consistent with) the pressure in the process chamber **16**. For example, a vacuum or
26 other pressure device can lower the pressure in the load lock. Once the load lock pressure is
27 sufficiently altered, a valve **34** or other mechanism can be altered to allow at least the first arm **18**

1 from the process chamber 16 to access the load lock 12, and specifically, wafers included in the
2 cassette 32.

3 [0035] It may thus be understood that the cassette can include one or more wafers, but in an
4 illustrative example, can include approximately twenty-five to fifty wafers. Referring to Figure
5 2, the first arm 18 can thus be configured to access wafers in the cassette 32 to allow the first arm
6 18 to retrieve a wafer. Those of ordinary skill will recognize that the cassette 32 may be
7 controlled and/or indexed and such control and/or indexing may be coordinated with the
8 operation of the first arm 18 to facilitate retrieval of a wafer. Figure 2 illustrates the second arm
9 30 in a standby mode, and although such may be the case for an initial wafer retrieved from a
10 cassette 32, as provided herein, for subsequent wafer retrievals, the second arm 30 may not be
11 positioned in a standby mode. Furthermore, the second arm 30 may be in another "standby"
12 position, such as in the orienter position.

13 [0036] Figure 3 presents the first arm 18 in the orienter position to allow the retrieved wafer
14 to be oriented for processing. Those of ordinary skill in the art will recognize that the orienter 20
15 can be controlled or otherwise operated in the illustrated systems to allow for the orienter 20 to
16 be vertically aligned with at least the first arm 18 when the first arm 18 is in the orienter position,
17 and accordingly, the orienter 20 can be adjusted as needed to interface with the first arm 18 to
18 allow orientation of the wafer. At such time, the second arm 30 may be in a standby position,
19 although as provided herein, the second arm 30 may be in another position such as the orienter
20 position.

21 [0037] Referring to Figure 4, the orienter 20 can facilitate a transfer of the wafer from the
22 first arm 18 to the second arm 30, where such first and second arms 18, 30 can be vertically
23 aligned to allow such transfer by the orienter 20. Accordingly, the illustrated orienter 20 can be
24 controlled for vertical displacement. It may be recognized that the vertical alignment of the first
25 and second arms 18, 20 can be performed at a time prior to the transfer of the wafer by the
26 orienter 20, and the disclosed methods and systems are not limited by the moment and/or timing
27 of the alignment unless otherwise provided herein. Accordingly, the alignment may occur during
28 orientation, or the alignment may occur prior to wafer orientation.

1 **[0038]** Figure 5 shows a delivery of the wafer by the second arm **30** for processing, where in
2 the illustrated systems, the processing area can be a platen **22**. As Figure 5 also illustrates, as the
3 second arm **30** is in the process position, the first arm **18** can be in a load lock position to retrieve
4 a second (or “next”) wafer from the cassette **32**. Accordingly, the cassette **32** can be controlled
5 or indexed in association with the first arm **18** to allow the first arm’s **18** retrieval of the next
6 wafer.

7 **[0039]** For the discussion herein, the “next” wafer can be understood to be the next wafer
8 retrieved for processing, and will be referred to as the “next” wafer until the wafer is processed,
9 whereupon such wafer can be referred to as the processed wafer.

10 **[0040]** Figure 6 indicates the first arm **18** in an orienter position while the second arm **30**
11 resides in an arbitrary standby position. As Figure 6 also indicates, the first wafer can be
12 processed **36** in the process chamber **16** while the next wafer may be oriented by orienter **20**.
13 Further, the second arm **30** may be in an alternate (e.g., orienter) position, as shown in Figure 7.
14 Figure 7 also accordingly indicates, similar to Figure 4, a transfer of the next wafer from the first
15 arm **18** to the second arm **30** where such transfer is facilitated by the orienter **20** as previously
16 provided herein with respect to Figure 4. Depending on the process system, the first wafer may
17 be processed **30** during such transfer of the second wafer from first arm **18** to second arm **30**.

18 **[0041]** Figure 8 indicates a movement of the first arm **18** and the second arm **30** to the
19 process position after a transfer of the next wafer to the second arm **30** and after processing of the
20 first wafer (now the “processed” wafer). Although Figure 8 indicates a simultaneous movement
21 of the first and second arms **18, 30** from an orienter position to a process position, such
22 movement can be non-simultaneous. In a configuration according to Figure 8, the first or
23 processed wafer can be transferred from and/or by the processing system to the first arm **18** and
24 the next wafer can be delivered to the processing system by the second arm **30**. Such
25 first/processed and next wafer transfers between the processing system, first arm **18**, and second
26 arm **30** can be coordinated to eliminate interface between the processed and next wafers.
27 Accordingly, for example, in an ion implantation system, a platen **22** can be controlled or

otherwise employed to transfer the first wafer to the first arm 18 for removal from processing, while thereafter, the platen 22 can retrieve the next wafer from the second arm 30.

[0042] Figure 9 indicates that once the platen 22 transfers the first or processed wafer to the first arm 18, the first arm 18 can return to an orienter position while the second arm 30 can remain in the process position to allow the platen 22 to transfer the next wafer from the second arm 30. The first or processed wafer can thus also be returned to the cassette 32 in the left load lock 12, as shown by Figure 10. Such illustration thus indicates that the cassette 32 can be controlled or indexed to facilitate a return of the first or processed wafer. Figure 10 also shows that upon delivery of the next wafer to the platen 22, the second arm 30 can return to a standby or other position that is not the process position.

[0043] Figure 11 illustrates the next wafer being processed 36 in the process chamber 16 while the first arm 18 is in the orienter position, or retracted from the cassette 32, and the second arm 30 is in a standby position. Accordingly, the Figure 11 cassette 32 can be controlled or indexed to facilitate a third wafer retrieval, which can now be referred to as the “next” wafer, where such retrieval of a third or next wafer by the first arm 18 is illustrated in Figure 12. Such third or next wafer retrieval from the cassette 32 in the load lock 12 can be performed during processing 36 of the second wafer (which is now the “processed” wafer), where the first arm can return to an orienter position as shown in Figure 13 to interface the third or next wafer with the orienter 20, and to thereafter facilitate a transfer of the third or next wafer by the orienter 20, where such transfer is from the first arm 18 to the second arm 30 as provided previously herein with respect to Figures 4 and 7, and as shown in Figure 14, where such transfer can occur during processing 36 of the second or processed wafer.

[0044] One of ordinary skill will thus recognize that the methods of Figures 8 through 14 can be repeated in an iterative manner to sequentially process wafers in the cassette 32 in the left load lock 12, where as provided previously herein, sequential processing does not imply an order of processing. Accordingly, references to the next and processed wafers can continue as wafers are retrieved and processed, with wafers being referred to as the “next” wafer from retrieval from the

cassette 32 through a processing 36 in the process chamber 16, whereupon such processing causes the “next” wafer to be referred to as the “processed” wafer.

[0045] The methods and systems are thus not specific to a certain wafer retrieval sequence, and such sequence can be based on a given system. Further, some embodiments may not process all wafers in the cassette. Additionally, although the illustrated methods and systems indicate that the first arm 18 was vertically displaced in a certain direction relative to the second arm 30, other embodiments may reverse the configuration. Similarly, other embodiments may provide for non-vertical alignment of arms 18, 30, orienter 20, and/or platen 22.

[0046] When a cassette from, for example, the left load lock 12 of Figure 14, is processed, the methods and systems described herein can be applied to the right load lock 14, and/or another load lock. During a processing of, for example, the right load lock 14 as provided herein with respect to Figures 1-14, the left load lock 12 can be isolated from the processing chamber, pressurized in accordance with the loading station, and the cassette 32 can be removed from the load lock 12. Further, a new cassette 32 can be loaded from the loading station to the left load lock 12, the left load lock 12 can be isolated, the left load lock can be evacuated in accordance with the processing chamber 16, and the load lock valve 34 can be opened to facilitate processing of the left load lock cassette 32 upon completion of the right load lock cassette. Accordingly, the methods and systems allow processing of one cassette in a first load lock while another cassette is load lock-processed (e.g., isolated from processing chamber, vented, interchanged, evacuated, valve opened, etc.) in a second load lock.

[0047] Further, it can be recognized that while the wafer processing described relative to Figures 1-14 was performed on the cassette wafers in the left load lock 12, the right load lock 14 could be performing load lock processing, including for example, isolation from the processing chamber 16, venting the right load lock 12, changing and/or replacing the right load lock cassette, isolating the right load lock 12, evacuating the right load lock 12, opening the load lock valve to expose the right load lock to the processing chamber 16, etc. Also, although not otherwise shown in the illustrations, one of ordinary skill thus can recognize that the methods and systems include first and second arms to process the wafers from the right load lock cassette, where such

first and second arms can be the same as or different from the first and second arms **18, 30** for processing the left load lock cassette. Accordingly, some embodiments can use a single set of first and second arms **18, 30** to access and/or process different load locks, while some embodiments may associate different first and second arms for processing different load locks.

[0048] Figure 15 provides one illustration of a disclosed system and method. As shown in Figure 15, a first wafer can be retrieved from a cassette by the first arm **100**, oriented **102**, transferred to the second arm **104**, and delivered for processing using the second arm **106**. While the first wafer is being processed **108**, a second or “next” wafer can be retrieved from the cassette using the first arm **110**, oriented **112**, and transferred to the second arm **114**. The first wafer, now the processed wafer, can be removed from processing using the first arm **116** to allow the second arm to deliver the next wafer for processing **118**. While the next wafer is processed **120**, the processed wafer can be returned to the cassette using the first arm **122**, and based on whether unprocessed wafers remain in the cassette **124**, the first arm can retrieve a “next” wafer from the cassette **126**, orient the next wafer **112**, and transfer the next wafer from the first arm to the second arm **114**. Such processing can continue according to Figure 15 until a desired number of wafers in the cassette are processed **124**. When the cassette does not include wafers for which processing is desired **124**, a next load lock that includes a cassette of at least one unprocessed wafer can be selected **128**, and processing **100** can continue on such next load lock cassette as provided in Figure 15. Further, load lock processing can be performed **130** on the load lock that contains the processed wafers, where such load lock processing can include isolating the load lock, venting, removing a cassette, replacing a cassette, inserting a cassette, evacuating the load lock, open the load lock valve, etc. Accordingly, those of ordinary skill will recognize that load lock processing can be performed on one or more load locks while wafer processing can be performed on another load lock. Further, it can be understood herein that the methods and systems illustrated by Figure 15 can be performed in parallel, for example, as wafer processing **108** and **120** can be performed in parallel with next wafer retrieval, orienting, and transferral **110-114** and **122-114**, respectively.

1 **[0049]** Those of ordinary skill will also recognize that although the methods and systems
2 presented an embodiment where during processing of a processed wafer, a next wafer is
3 retrieved, oriented, and transferred from the first arm to the second arm, some methods and
4 systems may include shorter processing times such that processing may not coincide completely
5 with retrieval, orienting, and transferral. Accordingly, in some embodiments, processing may
6 complete before retrieval, orienting, and transferral **110, 112, 114**, while in other embodiments,
7 processing may not complete until after retrieval, orienting, and transferral **110, 112, 114**, and
8 thus may indicate a delay until removal **116** and/or a measurement or other means to indicate
9 when processing is complete.

10 **[0050]** Figures 16A-16C, show a schematic representation of another embodiment according
11 to the disclosed methods and systems for handling wafers. Figures 16A- 16C show portions of a
12 wafer processing system that includes a left load lock **12** and right load lock **14**. As previously
13 provided herein, the methods and systems will be described relative to the left load lock **12** with
14 the understanding that the methods and systems can be applied to the right load lock **14**. The
15 Figures 16A-16D illustrate positions that may be engaged by a first arm **52** and a second arm **54**
16 that can access the left load lock **12**. As will be provided herein, the first and second arms **52, 54**
17 can be positioned in positions that include at least a load lock position to allow the first and
18 second arms **52, 54** to retrieve and/or return a wafer from/to the cassette **32** in the left load lock
19 **12**, an orienter position to allow the first and second arms **52, 54** to interface with at least an
20 orienter **20**, and a process position to allow the first and second arms **52, 54** to place a wafer in
21 and/or retrieve a wafer from a process chamber **16**.

22 **[0051]** Figure 16A can illustrate a first arm **52** in the orienter position to allow the retrieved
23 wafer to be oriented for processing. Those of ordinary skill in the art will recognize that the
24 orienter **20** can be controlled or otherwise operated in the illustrated systems to allow for the
25 orienter **20** to be vertically aligned with the first and second arms **52, 54** when the first and
26 second arms **52, 54** are in the orienter position, and accordingly, the orienter **20** can be adjusted
27 as needed to interface with the first and second arms **52, 54** to allow orientation of the wafer. At

such time as the first arm 52 is in the orienter position, the second arm 54 may be in the process position to retrieve a processed wafer from platen 22.

[0052] Referring to Figure 16B, first arm 52 can rotate to the process position to load the retrieved wafer onto platen 22. Second arm 54 can rotate to the orienter position. It can be understood that clearance between first and second arms 52, 54 can be arranged to allow a distance that facilitates independent operation when vertically aligned, while recognizing that a reduced vertical distance between the first and second arms 52, 54 may reduce processing time to transfer wafers between the first and second arms 52, 54 and the orienter 20 and the platen 22, as well as time to index wafer cassette 32. Although such vertical distance between such arms 52, 54 can thus vary based on system characteristics, in one embodiment, when vertically aligned, the first and second arms 52, 54 can be separated by less than approximately five-eighths to one-half of one inch.

[0053] Once the retrieved wafer is loaded onto platen 22, first arm 52 can return to the orienter position, or to a standby position such that the retrieved wafer can be processed 36, as previously described, while the second arm 54 can return the processed wafer to the wafer cassette 32, as illustrated in Figure 16C. As previously described, one of ordinary skill may recognize that the chamber 16 is shown to be enlarged to accommodate the first arm 52, which may be understood to be illustrated in one of the aforementioned standby positions. It can be understood that such enlargement of the process chamber 16 is optional, and in some embodiments, such enlargement may not be necessary to accommodate one or more standby positions for the first and second arms 52, 54.

[0054] In one embodiment, shown in Figure 16C, first and second arms 52, 54 can be mounted on or otherwise connected to a carriage 56 that can facilitate movement of first and second arms 52, 54 into and out of load lock 12 for return and retrieval of wafers to and from wafer cassette 32. In other embodiments, the second arm 54 can be mounted to or otherwise connected to carriage 56 and the first arm 52 can be mounted on or otherwise connected to a second carriage 58, as shown in phantom in Figure 16C, with carriages 56, 58 being configured for separate movement of the first and second arms 52, 54. In such embodiments, the standby

position for the first arm **52** can include the orienter position, as indicated in phantom as **52'** in Figure 16C, while the second arm **54** can return the wafer to wafer cassette **32**, though it can be understood that other of the aforementioned standby positions can be utilized. Wafer cassette **32** can be indexed, such that second arm **54** can retrieve a next wafer for processing.

[0055] The process can be repeated, as described further below with respect to Figure 17, with the positions of the first and second arms **52**, **54** being alternated in the Figures 16A-16C. As shown in Figure 17, a first wafer can be retrieved from a cassette by the first arm **200**, oriented **202**, and delivered for processing using the first arm **204**. While this wafer is being oriented, a second or processed wafer can be removed from processing using the second arm **206**.

The first arm can deliver the first wafer for processing **208**, while the second arm returns the next wafer to the cassette **210**. Based on whether unprocessed wafers remain in the cassette **212**, the second arm can retrieve a "next" wafer from the cassette **214** for orientation of the "next" wafer **216**, while the first wafer is processing. The first wafer, now the processed wafer, can be removed from processing using the first arm **218** to allow the second arm to deliver the next wafer for processing **220**. While the next wafer is processed **222**, the processed wafer can be returned to the cassette using the first arm **224**, and based on whether unprocessed wafers remain in the cassette **226**, the first arm can retrieve a "next" wafer from the cassette **200**, orient the next wafer **202**, and deliver the next wafer for processing **204**. Such processing can continue according to Figure 17 until a desired number of wafers in the cassette are processed **212**. When the cassette does not include wafers for which processing is desired **212**, a next load lock that includes a cassette of at least one unprocessed wafer can be selected **228**, and processing **200** can continue on such next load lock cassette as provided in Figure 17. Further, load lock processing can be performed **230** on the load lock that contains the processed wafers, where such load lock processing can include isolating the load lock, venting, removing a cassette, replacing a cassette, inserting a cassette, evacuating the load lock, open the load lock valve, etc. Accordingly, those of ordinary skill will recognize that load lock processing can be performed on one or more load locks while wafer processing can be performed on another load lock. Further, it can be understood herein that the methods and systems illustrated by Figure 17 can be performed in

parallel, for example, as wafer processing **208** and **222** can be performed in parallel with return of a processed wafer to the cassette, next wafer retrieval and orienting, **210-216** and **224, 200-204**, respectively.

[0056] Those of ordinary skill will also recognize that although the methods and systems presented an embodiment where during processing of a processed wafer, a processed wafer is returned, and a next wafer is retrieved and oriented, some methods and systems may include shorter processing times such that processing may not coincide completely with return, retrieval, and orienting. Accordingly, in some embodiments, processing may complete before return, retrieval, and orienting, **210, 114, 216**, while in other embodiments, processing may not complete until after return, retrieval, and orienting, **210, 214, 216**, and thus may indicate a delay until removal **218** and/or a measurement or other means to indicate when processing is complete.

[0057] What has thus been described are systems and methods for handling wafers that include retrieving a first wafer from a wafer cassette using a first arm, transferring the first wafer from the first transfer arm to a second arm, delivering the first wafer for processing to a process chamber using the second arm, removing the first wafer from the process chamber using the first arm, and, returning the first wafer to the cassette using the first arm.

[0058] The methods and systems described herein are not limited to a particular hardware or software configuration, and may find applicability in many computing or processing environments. For example, the control of the cassette interchanges, evacuation and venting, load lock valves, orienters, processing systems (e.g., platen, ion implantation, etc.), and the arms, can be implemented in hardware or software, or a combination of hardware and software. The methods and systems can be implemented in one or more computer programs, where a computer program can be understood to include one or more processor executable instructions. The computer program(s) can execute on one or more programmable processors, and can be stored on one or more storage medium readable by the processor (including volatile and non-volatile memory and/or storage elements), one or more input devices, and/or one or more output devices. The processor thus can access one or more input devices to obtain input data, and can access one or more output devices to communicate output data. The input and/or output devices can include

one or more of the following: Random Access Memory (RAM), Redundant Array of Independent Disks (RAID), floppy drive, CD, DVD, magnetic disk, internal hard drive, external hard drive, memory stick, or other storage device capable of being accessed by a processor as provided herein, where such aforementioned examples are not exhaustive, and are for illustration and not limitation.

[0059] The computer program(s) is preferably implemented using one or more high level procedural or object-oriented programming languages to communicate with a computer system; however, the program(s) can be implemented in assembly or machine language, if desired. The language can be compiled or interpreted.

[0060] As provided herein, the processor(s) can thus be embedded in one or more devices that can be operated independently or together in a networked environment, where the network can include, for example, a Local Area Network (LAN), wide area network (WAN), and/or can include an intranet and/or the Internet and/or another network. The network(s) can be wired or wireless or a combination thereof and can use one or more communications protocols to facilitate communications between the different processors. The processors can be configured for distributed processing and can utilize, in some embodiments, a client-server model as needed. Accordingly, the methods and systems can utilize multiple processors and/or processor devices, and the processor instructions can be divided amongst such single or multiple processor/devices.

[0061] The device(s) or computer systems that integrate with the processor(s) can include, for example, a personal computer(s), workstation (e.g., Sun, HP), personal digital assistant (PDA), handheld device such as cellular telephone, laptop, handheld, or another device capable of being integrated with a processor(s) that can operate as provided herein. Accordingly, the devices provided herein are not exhaustive and are provided for illustration and not limitation.

[0062] References to “a processor” or “the processor” can be understood to include one or more processors that can communicate in a stand-alone and/or a distributed environment(s), and can thus can be configured to communicate via wired or wireless communications with other processors, where such one or more processor can be configured to operate on one or more processor-controlled devices that can be similar or different devices. Furthermore, references to

1 memory, unless otherwise specified, can include one or more processor-readable and accessible
2 memory elements and/or components that can be internal to the processor-controlled device,
3 external to the processor-controlled device, and can be accessed via a wired or wireless network
4 using a variety of communications protocols, and unless otherwise specified, can be arranged to
5 include a combination of external and internal memory devices, where such memory can be
6 contiguous and/or partitioned based on the application. Accordingly, references to a database can
7 be understood to include one or more memory associations, where such references can include
8 commercially available database products (e.g., SQL, Informix, Oracle) and also proprietary
9 databases, and may also include other structures for associating memory such as links, queues,
10 graphs, trees, with such structures provided for illustration and not limitation.

11 **[0063]** References to a network, unless provided otherwise, can include one or more intranets
12 and/or the Internet.

13 **[0064]** Many additional changes in the details, materials, and arrangement of parts, herein
14 described and illustrated, can be made by those skilled in the art. Accordingly, it will be
15 understood that the following claims are not to be limited to the embodiments disclosed herein,
16 can include practices otherwise than specifically described, and are to be interpreted as broadly as
17 allowed under the law.